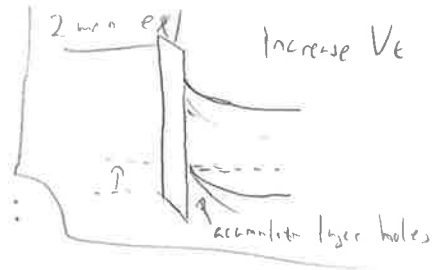


$I_D(V_{GS})$ for small V_{GS} (page 42-43)



At position y along channel:

$$I_D = W \cdot Q_I(y) \cdot v_d(y) = W \cdot Q_I(y) \cdot \mu_n \cdot E(y)$$

width \uparrow charge/area \uparrow velocity \uparrow electron mobility ($< \mu_{bulk}$) \uparrow surface \uparrow electron field in y -direction

$$Q_I(y) = C_{ox} (V_{GS} - V(y) - V_t) \quad (\text{assume } V_{GS} - V(y) > V_t)$$

capacitance/area \uparrow voltage at pos. y w.r.t. source \uparrow need to overcome V_t to get any inversion charge

$$E(y) = \frac{dV}{dy}$$

$$= W C_{ox} (V_{GS} - V(y) - V_t) \cdot \mu_n \cdot \frac{dV}{dy} \quad \text{integrate}$$

$$\int_0^L I_D \cdot dy = \int_0^{V_{DS}} W \mu_n C_{ox} (V_{GS} - V - V_t) dV$$

$$I_D \cdot L = W \cdot \mu_n \cdot C_{ox} \cdot \left[V_{GS} \cdot V - \frac{V^2}{2} - V_t \cdot V \right]_0^{V_{DS}}$$

$$I_D = \frac{W \cdot \mu_n \cdot C_{ox}}{L} \cdot \left(2(V_{GS} - V_t) \cdot V_{DS} - V_{DS}^2 \right) \quad (*)$$

I_d (high V_{DS}) pinch-off

(*) not for $V_{DS} > V_{GS} - V_t$

Channel voltage at pinch-off point is $V_{GS} - V_t$.

Integrate r.h.s. $0 \rightarrow V_{GS} - V_t$ instead

$$I_D = \frac{W}{L} \frac{\mu_n C_{ox}}{2} \left(2(V_{GS} - V_t)(V_{GS} - V_t) - (V_{GS} - V_t)^2 \right) =$$

$$= \frac{W}{L} \frac{\mu_n C_{ox}}{2} (V_{GS} - V_t)^2 \quad (***) \quad \underline{\text{independent of } V_{DS}}$$

I_D with channel length modulation

Replace L with $L_{eff} = L - X_d$, X_{eff} depends on V_{DS}

$$I_D = \frac{W}{L_{eff}(V_{DS})} \frac{\mu_n C_{ox}}{2} (V_{GS} - V_t)^2$$

$$\frac{\partial I_D}{\partial V_{DS}} = - \frac{W}{L_{eff}^2} \frac{\mu_n C_{ox}}{2} (V_{GS} - V_t)^2 \cdot \frac{dL_{eff}}{dV_{DS}} =$$

$$= - \frac{I_D}{L_{eff}} \cdot \frac{d(L - X_d)}{dV_{DS}} = \frac{I_D}{L_{eff}} \cdot \frac{dX_d}{dV_{DS}}$$

define $\lambda = \frac{\frac{\partial I_D}{\partial V_{DS}}}{I_D} \leftarrow$ how large part of I_D change with increasing V_{DS}

$$\lambda = \frac{1}{L_{eff}} \cdot \frac{dX_d}{dV_{DS}}$$

modify (***) $I_D = \frac{W}{L} \frac{\mu_n C_{ox}}{2} (V_{GS} - V_t)^2 (1 + \lambda V_{DS}) \leftarrow$ additional contribution $r_o = \frac{dI_D}{dV_{DS}} = \frac{I_D}{\lambda V_{DS}}$ \rightarrow output resistance (2)

Example: MOSFET with channel length modulation
0,0020

~~Linear region~~

$$I_D = \frac{0,135 \cdot 3 \cdot 10^{-3}}{2} \cdot \frac{50 \cdot 10^{-6}}{5 \cdot 10^{-6}} \left(2(V_{GS} - V_t) V_{DS} - V_{DS}^2 \right)$$

$$= 0,0020 \cdot \left(2(V_{GS} - V_t) V_{DS} - V_{DS}^2 \right) =$$

1) $V_{GS} < V_t \rightarrow I_D = 0$ for all V_{DS}

2) $V_{GS} \geq V_t$ (ok)
 $V_{GS} = 2,5V$

$$V_{DS} = 0,5V \Rightarrow 0,5 < \overbrace{2,5 - 1} \rightarrow \text{linear region}$$

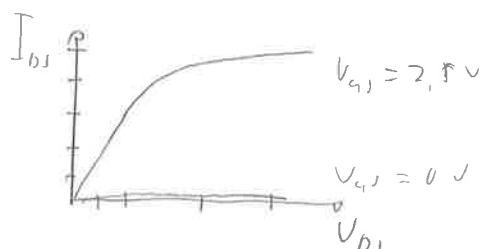
$$I_D = 0,002 \cdot \left(2 \cdot (2,5 - 1) 0,5 - 0,5^2 \right) = 2,5 \text{ mA}$$

$$V_{DS} = 1V, 1 < 2,5 - 1 \rightarrow \text{linear } I_D = 4 \text{ mA}$$

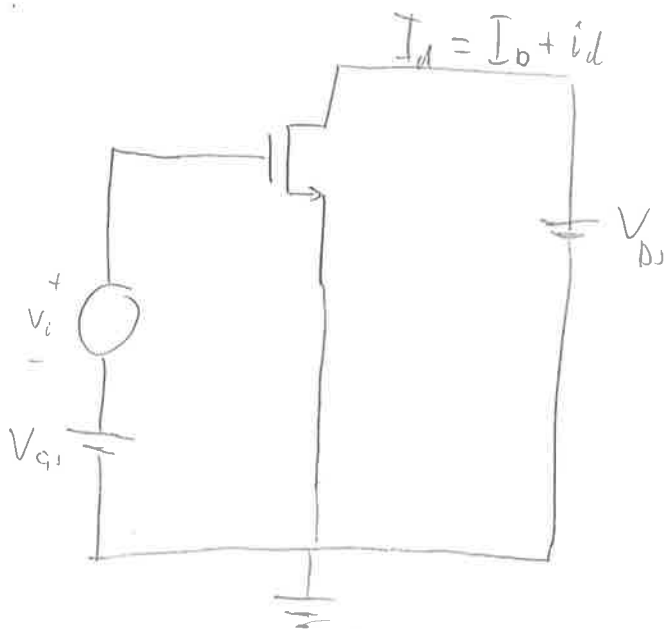
$$V_{DS} = 2V, 2 > 2,5 - 1 \rightarrow \text{saturation}$$

$$I_D = 0,002 (2,5 - 1)^2 (1 + 0,02 \cdot 2) = 4,7 \text{ mA}$$

$$V_{DS} = 3V, 3 > 2,5 - 1 \rightarrow \text{saturation } I_D = 4,8 \text{ mA}$$



Small signal model - transconductance



Transconductance

$$g_m = \frac{\partial I_D}{\partial V_{GS}} = \frac{\partial}{\partial V_{GS}} \left(\frac{\mu_n C_{ox}}{2} \cdot \frac{W}{L} (V_{GS} - V_t)^2 (1 + \lambda V_{DS}) \right) =$$

$$= \mu_n C_{ox} \cdot \frac{W}{L} (V_{GS} - V_t) (1 + \lambda V_{DS}) = \left\{ \text{small } \lambda \right\} = \mu_n C_{ox} \frac{W}{L} (V_{GS} - V_t)$$

$$= \sqrt{2 \mu_n C_{ox} \frac{W}{L} I_D} \Rightarrow g_m \propto \sqrt{I_D} \quad \left(\begin{array}{l} \text{for} \\ \text{BJT} \end{array} \right. g_m \propto I_D)$$

To get high g_m
 { thin oxide
 short gate length
 large width
 increase μ_n (11-V, strain)
 increase ϵ_{ox} (high-k)

Input resistance

∞ due to oxide $\rightarrow I_G = 0$ for low frequency

Output resistance

$$\frac{\partial I_D}{\partial V_{DS}} = \frac{1}{\lambda I_D} = r_o$$

